Magnesium Oxide \( \text{MgO} \)

Sputtering Targets

**Applications**
- Non-volatile Memory or Ferroelectric RAM
- Thin film capacitors

**Features**
- High purity
- Custom Sizes Available

**Process**
- Manufacturing
  - Cold pressed
  - Sintered
  - Indium bonded to backing plate
- Cleaning and final packaging
  - Cleaned for use in vacuum
  - Protection from environmental contaminants
  - Protection during shipment

**Options**
- 99.95% minimum purity
- Up to 12.0" Diameter Targets Available
- Planar Tiles Up to 8" X 5" for Larger Target Configurations
Specifications

Typical Analysis - 99.95% (3N5) Purity

Metallic Impurities, ppm by weight

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Theoretical Density | 3.58 g/cc
Typical Density | >3.1 g/cc
Sputter | RF, RF-R
Max Power Density (Watts/Square Inch) | 20
Melting Point | 2,852°C
Appearance | White/Yellow/Beige
Z Ratio | 0.411
Particle Size | D50

Advanced Engineering Materials

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